

PATENT
Attorney Docket No.: 728-208 (YOR9-2001-0270 US)

IN THE CLAIMS

1-11. (Previously Canceled)

12. (Currently Amended) An array of planar T-RAM cells comprising:

a plurality of T-RAM cells, said plurality of T-RAM cells being arranged in an array and fabricated over a substrate, each of said plurality of T-RAM cells including a buried vertical thyristor and a horizontally stacked pseudo-TFT transfer gate, said transfer gate including a source/drain and body formed in a polysilicon layer, said thyristor being buried underneath said transfer gate, wherein said transfer gate covers the entire top surface of said thyristor, and further wherein the top surface of said transfer gate forms a co-planar top surface of each said transfer gate of each said T-RAM cell.

13. (Previously Canceled)

14. (Original) The array according to Claim 12, wherein each of the plurality of T-RAM cells has a size of less than or equal to $8F^2$.

15. (Previously Amended) The array according to Claim 12, wherein said substrate is a semiconductor SOI or bulk wafer.

16. (Previously Amended) The array according to Claim 13, wherein a base of said thyristor is surrounded by a surrounded gate.

17. (Currently Amended) The array according to Claim 12, wherein said planar top surface of each T-RAM cell provides for simplified fabrication of wordlines, said wordlines being fabricated over said planar top surface of said T-RAM cells, said wordlines for interconnecting said T-RAM cells.

18-30. (Previously Canceled)

31. (Currently Cancelled)